

Amendments to the Specification

Please amend paragraph [0023] of the Specification as follows:

FIG. 2 is another illustration of the wavefront measurement apparatus of the present invention, particularly as it can be incorporated into a photolithographic system. As may be seen in **FIG. 2**, the source module **103** is placed on the reticle stage, and in one embodiment includes two orthogonally oriented gratings. The wavefront sensor (or sensor module **106**) is placed on the wafer stage and includes a 2-D grating **201** and a CCD detector **202** that is positioned below the 2-D grating. The projection optics (PO) **104** remain the same as [[doing]] during normal exposure operation.